

# IEUVI Optics Contamination and Lifetime TWG February 19, 2006

		<b>Start Time</b>	<b>End Time</b>
1	<b>Welcome / Registration</b>	<b>15</b>	9:45 AM 10:00 AM
2	Cap Layer Development Technology Mapping, led by Ming Fang (Intel Corp.)	<b>60</b>	10:00 AM 11:00 AM
3	in situ Metrology Technology Mapping, led by Shannon Hill (NIST) & Obert Wood (AMD/ SEMATECH)	<b>60</b>	11:00 AM 12:00 PM
4	Lunch	<b>60</b>	12:00 PM 1:00 PM
5	Lifetime Testing: past plans, current status, ideal test chamber led by Ginger Edwards ( Freescale/ SEMATECH) & Manish Chandhok (Intel Corp.)	<b>60</b>	1:00 PM 2:00 PM
6	Beta Specs Revisited, led by Ginger Edwards ( Freescale/ SEMATECH)	<b>30</b>	2:00 PM 2:30 PM
7	Critical Issue Voting Revisited, led by Ginger Edwards ( Freescale/ SEMATECH)	<b>30</b>	2:30 PM 3:00 PM
8	Break	<b>15</b>	3:00 PM 3:15 PM
9	Invited Talk: Paul Kirsch (IBM/ SEMATECH FEP Division): "High K Gate Materials Development & Metrology: Applicable Lessons for EUV Optics Cap Layer Development"	<b>30</b>	3:15 PM 3:45 PM
10	Invited Talk: Alain Diebold (Senior Fellow, SEMATECH): "Post-lifetime Testing Metrology for EUV Optics Cap Layers"	<b>30</b>	3:45 PM 4:15 PM
11	Invited Talk: Tim Hossain (Cerium Labs): "Sample Handling Issues and Related Metrology for EUV Optics Cap Layers"	<b>30</b>	4:15 PM 4:45 PM
12	Break	<b>10</b>	4:45 PM 4:55 PM
13	US Update: Tom Lucatorto, NIST	<b>20</b>	4:55 PM 5:15 PM
14	Japan Update: Yasuaki Fukuda, EUVA	<b>20</b>	5:15 PM 5:35 PM
15	Wrap / Assignment Action Items	<b>10</b>	5:35 PM 5:45 PM